

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



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| Atty. Dkt. No. | M# | Client Ref. |
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| 310701 | | P-1943.063-US |
| Applicant: HOFFMAN et al. | | |
| Appn. No.: 10/759,699 | | |
| Filing Date: January 19, 2004 | | |
| Examiner: M. HASAN | | Group Art Unit: 2873 |

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Date: November 22, 2004

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of

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Examiner *M. Hasan* Date Considered: *11/14/05*

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7/14/05

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